

TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT
(Under 37 CFR 1.97(b) and 1.97(e))

Docket No.
OSBE-101519

In Re Application Of: **Rahul Ganguli et al.**

SEP 03 2004

Application No.

10/646,356

Filing Date

August 22, 2003

Not yet assigned

Customer No.

30764

Group Art Unit

1752

Confirmation No.

8611

Title: **PHOTOMASK ASSEMBLY INCORPORATING A POROUS FRAME AND METHOD
FOR MAKING IT**

Address to:

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

37 CFR 1.97(b)

1. ☒ The Information Disclosure Statement submitted herewith is being filed within three months of the filing of a national application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits, or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114.

37 CFR 1.97(c)

2. ☐ The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(b), provided that the Information Disclosure Statement is filed before the mailing date of a Final Action under 37 CFR 1.113, a Notice of Allowance under 37 CFR 1.311, or an Action that otherwise closes prosecution in the application, and is accompanied by one of:

☐ the statement specified in 37 CFR 1.97(e);

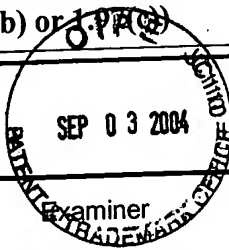
OR

☐ the fee set forth in 37 CFR 1.17(p).

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Payment of Fee

(Only complete if Applicant elects to pay the fee set forth in 37 CFR 1.17(p))

- ☐ A check in the amount of _____ is attached.
- ☒ The Director is hereby authorized to charge and credit Deposit Account No. 19-1853 as described below.
- ☐ Charge the amount of _____
- ☐ Credit any overpayment.
- ☒ Charge any additional fee required.
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Signature

James R. Brueggemann, Esquire

Registration No. 28, 286

Sheppard, Mullin, Richter & Hampton LLP

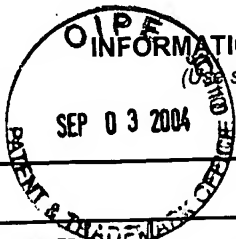
333 South Hope Street, 48th Floor

Los Angeles, California 90071

(213) 620-1780

Dated: August 31, 2004

CC:

**INFORMATION DISCLOSURE CITATION**

(Use several sheets if necessary)

ATTY DOCKET NO.

OSBE-101519

APPLICATION NO.

10/646.356

APPLICANT(S)

Rahul Ganguli et al.

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GROUP ART UNIT

1752

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	4,833,051	05/23/89	Imamura	430	5	
	5,344,677	09/06/94	Hong	428	14	
	5,529,819	06/25/96	Campi, Jr.	428	14	
	5,814,381	09/29/98	Kuo	428	14	
	6,099,792	08/08/00	Ganguli et al.	264	621	

U.S. PATENT APPLICATION PUBLICATIONS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	US 2004/0028269 A1	02/12/04	Yamabe et al.	382	144	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	WO 01/59522 A1	08/16/01	PCT				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

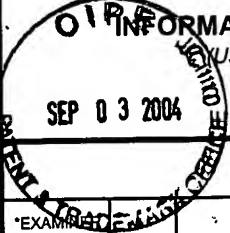
Kikugawa, S., Okada, K., Mishiro, H. and Sasuga, T., "Current Status of Hard Pellicle Development, Asahi Glass Co., Ltd., December 10, 2001, pp 1-14

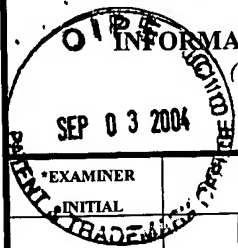
Laganza, Joseph, "157nm Reticle Handling Technology, Sematech TDR, December 12, 2001, pp 1-20

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

 <p>INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)</p>				ATTY DOCKET NO. OSBE-101519		APPLICATION NO. 10/646,356		
				Rahul Ganguli et al.				
				FILING August 22, 2003		GROUP ART 1752		
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
		6,507,390	01/14/03	Ivaldi	355	75		
		6,524,754	02/25/03	Eynon	430	5		
		6,593,034	07/15/03	Shirasaki	430	5		
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*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
			Cullins, Jerry, "LITJ360-157nm Mask Materials," International Sematech 157nm Technical Data Review, December 2001, pp 1-4					
			"Hard Pellicle Overview," International Sematech, February 4, 2002, pp 1-6					
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

"157nm Blank Status," International Sematech, February 4, 2002, pp 1-3

Purging," International Sematech, February 4, 2002, pp 1-11

"157 nm Cleaning/Handling," International Sematech, February 4, 2002, pp 1-7

Ganguli, Rahul, et al., "Sol-gel fabrication of high quality photomask substrates," Proceedings of SPIE, Vol. 4889, October 1, 2002, pp 32-39

Meixner, D. Laurence, et al., "Porous silica frame for deep UV lithography," Proceedings of SPIE, Vol. 4889, October 3, 2002, pp 450-456

Bhattacharyya, Kaustuve, et al., "Investigation of reticle defect formation at DUV lithography," Photomask, February 2003, Vol. 19, Issue 2, 7 pages

Meixner, D. Laurence, "Porous silica frame for deep UV lithography," Proceedings of SPIE, Vol. 5040, February 25, 2003, pp 1018-1024

Jeng, De-Yin, et al., "Porous Silica Pellicle Frame," Proceedings of SPIE, Vol. 5256, September 9, 2003, pp 213-221

EXAMINER

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